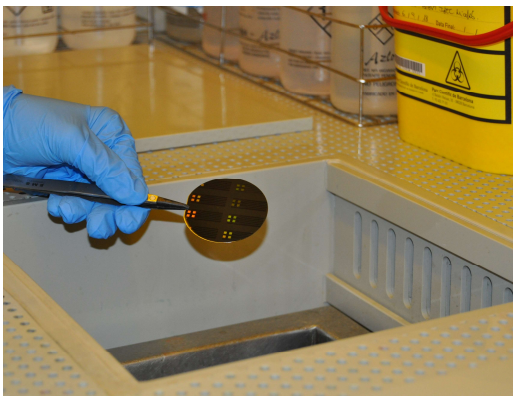




Manufacturer
QUIMIPOL

Chemical Bath



Chemical bench for wet etching and/or cleaning substrates

The bench is full equipped to process up to 4 inches wafers, in a comfortable and safe way.

It allows processes as:

- Cleaning of samples
- Lift-off processes
- Wet etching of materials
- Chemical surface functionalization

Technical specifications

- Full anticorrosive polypropylene bench and cabinets
- Laminar flow cabinet
- 190 mm x 190 mm baths for 4 inch wafer processes
- Baths with automatic drain of specific wastes (acid/basic)
- Drained bench for collection of accidental spills
- N₂, compressed air, vacuum and water sources
- Yellow light for white light sensitive processes
- Ultrasonic bath with 2 power levels and timer up to 120 min

Available material

- Etchers as Cr etchant, HF, etc.
- Developers
- Removers
- Silanes
- Acetone, Isopropanol, Ethanol, Deionized water and Milli-Q water
- Glassware and other clean room tools

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